

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	113	(gustaaf.in. near5 feltz.in.) (cheng-qun.in. near4 gui.in.) (johan.in. near4 hoefnagels.in.)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:12
L4	30468	((substrate wafer reticle mask) near4 (temperature heat\$3)) with (measur\$5 sens\$3 detect\$3 determin\$5)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:13
L5	39992	(substrate wafer mask reticle) with ((dimension\$3 near response) expand\$4 deform\$5 (spatial near distribution)) with (calculat\$3 determin\$5 predict\$3 model\$3 coefficient co\$efficient measur\$5)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:20
L6	1	3 and (4 and 5).clm.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:20
L7	1	3 and (4).clm.	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:20
L9	4476	4 with (area region portion section)	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:21
L10	357	5 and 9	US_PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:22

L11	176121	(different first second) near5 (area region portion section) near5 (substrate wafer mask reticle)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:22
L12	126	10 and 11	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:23
L13	84	@ad<= "20040329" and 12	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:23
L14	258209	(pattern\$3 form\$3 expos\$5 record\$3 project\$3) near5 (pattern image mark) near5 (substrate wafer mask reticle)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:23
L15	36	13 and 14	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:24
L16	21	(4 and 5 and 14).clm.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:25
L17	91973	(shape cross\$section\$3 size location position disposition disposed) near3 (beam light radiation illumination) with (correct\$3 adjust\$4 compensat\$3 chang\$3)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:27
L18	30	(9 and 5 and 17)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/06/22 20:27
L19	11	(4 and 5 and 14).clm.	US-PGPUB	OR	ON	2008/06/22 20:28
L20	1	(9 and 5 and 17).clm.	US-PGPUB	OR	ON	2008/06/22 20:28

6/22/2008 9:14:44 PM

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